2.2 Performance:

No	Item	Specification	Conditions
1	Resolution		
	(1)Conventional (2)1/2 Annular	(1) 0.50 μ m (2) 0.35 μ m	Positive photoresist, Film thickness: 1.0um
2	Lens Distortion	≦ ±50nm	37 points in-shot
3	Magnification Control Accuracy	≦ ±20nm	Measure at 3 intervals of
4	Maximum Exposure Area	22.0mm(Hor.)×22.0mm（Ver.）	INITIAL,HEAT 180 and COOL 240
5	Reticle Blind Setting Accuracy	17.92mm(Hor.)×25.2mm（Ver.） (within 31.11mm Dia) +0.4mm to +0.8mm	On reticle
6	Exposure Power	≧ 700mW/cm2	Measured after a new lamp is
7	Integrated Exposure Control	(1) ≦ ±1.0%	installed
	Accuracy (1)50mJ/cm2 or more (2)100mJ/cm2	(2) ≦ ±0.5%	Including exposure dose matching
8	Illumination Uniformity	Spec ≦ ±1.5%	Within exposure area, 5
9	Reticle Rotation	Ave + 3 σ ≦ 20nm	measurements Center of reticle rotation target
10	EGA Alignment Accuracy	Ave + 3 σ ≦ 100nm	value Overlay of resist image,
	(Chip center measurement)		EGA 5points
11	Array Orthogonality	≦ ±0.1sec	After software correction,
12	Stepping Precision	3 σ ≦ 70nm	Average of 3 wafers Measure 2 wafers
13	Wafer Pre-alignment Repeatability	3 σ ≦ 100 μ m	On the same wafer,
14	EGA Throughput	40.00sec/wafer(150mm)	60 measurements, Evaluate independently for each X,Y and θ EGA 5 points,
		60.00sec/wafer(200mm)	2nd exposure, Exp. Time = 0.13sec 32 shots (150mm) 60 shots (200mm)
15	Operational Test		(1)Consecutive 2nd printing on
	(1) Wafer System (2) Reticle System	(1)Success rate : ≧99% (2)Success rate: 100%	100 wafers (2)Once for every slot
16	DOF (Depth of Focus)	(1)CD ≤ 0.10μm over 1.20μm	5 points V/H
	(1) 0.50 μ m L&S (2) 1.00 μ m L&S	DOF range (2)CD ≤ 0.20μm over 3.00μm DOF range	Exposure condition: 0.50μm L&S (CEv) ⇒ 0.50±0.02μm (at best focus) 1.00μm L&S (CEv) ⇒ 1.00±0.05μm (at best focus)

2 Performance：

RFQ：		
1. 2.2 Performance No.4		
Specification 17.92nm 17.96nm 2. 2.2 Performance 中 No.10		
EGA Alignment Accuracy Alignment Accuracy		
3. 2.2 Performance No.14		
Item EGA Throughput Throughput		
删除 Specification 40.00sec/wafer(150mm)		
更改 Specification 60.00sec/wafer(200mm)60.00wph(200mm)删除		
Condition 32 shots (150mm)		